



# AZ 1529 photoresist

Product	AZ 1529 photoresist
Manufacturer	EMD Performance Materials Corp.
Composition	65–70% <a href="#">1-methoxy-2-propanol acetate</a> , 5–10% <a href="#">diazonaphthoquinonesulfonic ester</a> , 0 - 0.3% <a href="#">2-methoxy-1-propanol acetate</a> , 25–30% <a href="#">cresol novolak resin</a> ; liquid
Synonyms	
Typical Uses	Positive-tone photoresist for broadband and g/h/i-line exposure
Hazards	<div></div> <p>202</p> <p>Serious eye damage/eye irritation <b>CATEGORY 2A</b>, Flammable liquids <b>CATEGORY 3</b>, Specific target organ toxicity – single exposure <b>CATEGORY 3</b></p>
Storage	Working volumes in amber bottles, stored in primary litho area; stock bottles in resist fridge outside W1-040
Disposal	Solid: Organic waste / organic sharps waste containers in primary or secondary litho areas. Liquid: solvent waste bottles in litho wet decks or wet decks 1A/1B/2A.
Comments	<a href="#">Standard recipe</a> yields ~3.4 µm resist thickness.
Status	<b>STOCKED</b>



## Check First

Please contact a nanoFAB staff member for uses not listed above.

## Additional information

- [AZ 1500 series datasheet](#)